7 17 1			1.55	T
L Number	Hits		DB	Time stamp
1 -	2	jp-2000035665-\$.did.	USPAT; US-PGPUB;	2003/07/09 08:57
			EPO; JPO;	
			DERWENT	
_	2	(("20020068237") or ("20020068236")).PN.	US-PGPUB	2003/07/09 08:57
	1975440	i e e e e e e e e e e e e e e e e e e e	USPAT;	2003/07/07 12:06
	19/3440	Testi Testsc photoresisc	US-PGPUB;	2003/07/07 12:00
			EPO; JPO;	
			DERWENT	
_	16077	(photoacid acid) near generat\$3	USPAT;	2003/07/07 12:06
	100,,	(photoacia acia, near generacy)	US-PGPUB;	2003,01,01 12100
			EPO; JPO;	
			DERWENT	
-	78586	photosensitizer sensitizer	USPAT;	2003/07/07 12:05
			US-PGPUB;	
		solvent East Search	EPO; JPO;	
		Tast Joacol	DERWENT	
-	1008314	solvent houst solvent	USPAT;	2003/07/03 13:46
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	1234	1 ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' ' '	USPAT;	2003/07/03 13:49
		acid) near generat\$3) and (photosensitizer	US-PGPUB;	
		sensitizer) and solvent	EPO; JPO;	
			DERWENT	
-	5890	benzopyran	USPAT;	2003/07/07 12:06
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	25		USPAT;	2003/07/07 11:40
		acid) near generat\$3) and (photosensitizer	US-PGPUB;	
		sensitizer) and solvent) and benzopyran	EPO; JPO;	
			DERWENT	
-	155	IMAI-G IMAI-GENICHI IMAI-GENJI	USPAT;	2003/07/08 16:22
			US-PGPUB;	
			EPO; JPO;	
	_	(TOP T G TOP T GROVE TOP T GROVET)	DERWENT	0000/05/05 10 01
-	6	(===== = ==== ==== === = === = = = = =	USPAT;	2003/07/07 12:01
		benzopyran	US-PGPUB;	
			EPO; JPO;	
_	78586	photosensitizer sensitizer	DERWENT	2003/07/07 12:06
-	70300	photosensitizer sensitizer	USPAT; US-PGPUB;	2003/07/07 12:06
		- Alle WOLLING	EPO; JPO;	
		() IVII ICEATUVE ~	DERWENT	
<u> </u>	5890 '	benzopyran	USPAT;	2003/07/07 12:06
	5050		US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	61	(photosensitizer sensitizer) same	USPAT;	2003/07/07 12:08
	_	benzopyran	US-PGPUB;	
		_ 	EPO; JPO;	
			DERWENT	
-	16077	(photoacid acid) near generat\$3	USPAT;	2003/07/07 17:04
		_	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	1975440	resin resist photoresist	USPAT;	2003/07/07 12:06
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	7	((photosensitizer sensitizer) same	USPAT;	2003/07/07 12:07
		benzopyran) and ((photoacid acid) near	US-PGPUB;	
		generat\$3) and (resin resist photoresist)	EPO; JPO;	
	_		DERWENT	
-	3	(((photosensitizer sensitizer) same	USPAT;	2003/07/07 12:07
		benzopyran) and ((photoacid acid) near	US-PGPUB;	
		generat\$3) and (resin resist photoresist))	EPO; JPO;	
		not ((IMAI-G IMAI-GENICHI IMAI-GENJI) and	DERWENT	
L		benzopyran)	l	

benzopyran) and (resin resist photoresist) US-PGUB; PO JPO DERMENT Series PO J					
13	-	20	((photosensitizer sensitizer) same benzopyran) and (resin resist photoresist)		2003/07/07 12:08
benzopyran and (regin regist photocesist 1) not (((IMAI-GIMAI-GMINI) MAIN				DERWENT	
Cresin resist photoresist	-	13	benzopyran) and (resin resist photoresist)) not (((IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran) (((photosensitizer sensitizer) same benzopyran) and	US-PGPUB; EPO; JPO;	2003/07/07 12:10
S.P.GPUB; EPO, JPO; DERWENT USPAT; US-PGPUB; EPO,					
2 jp-08334897-\$.did. USPAT: US-PGUDIS EPO, JPO, DERNemT US-PGUDIS EPO, JPO, DERNemT USPAT: US-PGUDIS EPO, JPO, DERNemT US-PGUDIS EPO, JPO, DERNemT USPAT: US-PGUDIS EPO, JPO, DERNemT USPAT	-	0	jp-8334897-\$.did.	US-PGPUB; EPO; JPO;	2003/07/07 12:10
2 jp-11212252-\$.did. or jp-2000275823 or jp-200056450 jp-200056450 jp-2000275823 or jp-200056450 jp-200056450 jp-2000275823 or jp-200056450 jp-200056450 jp-2000275823 or jp-200005665-\$.did. USPAT; USPEUB; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPEUB; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPEUB; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPEUB; USPAT;	-	2	jp-08334897-\$.did.	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 12:26
G	-	2		USPAT; US-PGPUB; EPO; JPO;	2003/07/07 12:27
2 jp-2000035665-\$.did. USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; US-PGPUB	- ·	6	jp-2000056450) jp-09138502-\$.did.	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 12:27
1	-	2	jp-2000035665-\$.did.	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 12:49
1 (titanocene adj compound) same (\$5acid near generator) - 0 ((titanocene adj compound) same (\$5acid near generator)) not (titanocene same (\$5acid near generator)) not (titanocene same (\$5acid near generator)) - 51 (radical adj generator) same ((acid USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; U	-	2	titanocene same (\$5acid near generator)	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 13:47
- 0 ((titanocene adj compound) same (\$5acid near generator)) not (titanocene same (\$5acid near generator)) not (titanocene same (\$5acid near generator)) - 51 (radical adj generator) same ((acid photoacid) near generator) - 900 (resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer) - 509 ((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative photocurable curable cur\$5 negative consolinkable crosslinked crosslink (cross adj link\$4) cross-link\$4 - 509 (((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4 - 4167371 drying heat-treat\$5 (heat\$5) bak\$4 USPAT; USPAT; USPAT; USPAGUB; Pre-bake\$4	-	1		USPAT; US-PGPUB; EPO; JPO;	2003/07/07 13:47
- 51 (radical adj generator) same ((acid photoacid) near generator) - 900 (resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative (photosensitizer sensitizer)) and negative (crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4 - 509 (((resin resist photoresist binder) and ((photoacid acid) near generator) and (photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4) - 4167371 dry drying heat-treat\$5 (heat\$5) bak\$4 USPAT; US-PGPUB; Pre-bake\$4	-	0	generator)) not (titanocene same (\$5acid	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 13:48
- 900 (resin resist photoresist binder) and (photoacid acid) near generator) and (photosensitizer sensitizer) - 509 ((resin resist photoresist binder) and (photoacid acid) near generator) and (photoacid acid) near generator) and (photosensitizer sensitizer)) and negative photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4 - 509 (((resin resist photoresist binder) and (photoacid acid) near generator) and (photoacid acid) near generator) and (photoacid acid) near generator) and (photosensitizer sensitizer)) and negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4 - 4167371 dry drying heat-treat\$5 (heat\$5) bak\$4 USPAT; pre-bake\$4 USPAT; U	-	51		USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:24
- 509 ((resin resist photoresist binder) and (photoacid acid) near generator) and (photosensitizer sensitizer)) and negative photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4 - 509 (((resin resist photoresist binder) and (photoacid acid) near generator) and (photosensitizer sensitizer)) and negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4 - 4167371 dry drying heat-treat\$5 (heat\$5) bak\$4	-	900	((photoacid acid) near generator) and	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 17:03
- 3797882 photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4 - 509 (((resin resist photoresist binder) and ((photoacid acid) near generator) and ((photosensitizer sensitizer)) and negative and ((photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4) - 4167371 dry drying heat-treat\$5 (heat\$5) bak\$4 USPAT; pre-bake\$4 USPAT;		509	((photoacid acid) near generator) and	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:26
- 509 (((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and (photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4) - 4167371 dry drying heat-treat\$5 (heat\$5) bak\$4 USPAT; pre-bake\$4	-	3797882	crosslinkable crosslinked crosslink (cross	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:27
- 4167371 dry drying heat-treat\$5 (heat\$5) bak\$4 USPAT; 2003/07/07 14:30 pre-bake\$4 US-PGPUB;	-	509	((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and (photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:28
DERWENT	-	4167371	dry drying heat-treat\$5 (heat\$5) bak\$4	US-PGPUB; EPO; JPO;	2003/07/07 14:30

-	4553605	coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))	USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:31
-	1655136	irradiate irradiating expose exposure exposing exposed irradiated irradiation	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:31
-	1640490	develop development developing developed]	DERWENT USPAT; US-PGPUB; EPO; JPO;	2003/07/07 14:32
-	360309	(visible adj light) "VIS"	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:32
-	57817	(dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:33
-	208	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:37
	50	((VISIBLE add light) "VIS") ((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS"))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:41
-	27	((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS"))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))	USPAT; EPO; JPO; DERWENT	2003/07/07 15:48
-	2	("6033826").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 15:48
_	1	(("6033826").PN.) and (generator) and (\$5sensitizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 16:31

-	32	pyrene same (benzopyran)	USPAT; US-PGPUB;	2003/07/07 15:54
			EPO; JPO; DERWENT	
-	18	(((((resin resist photoresist binder) and	USPAT;	2003/07/07 17:03
		((photoacid acid) near generator) and	US-PGPUB;	
		(photosensitizer sensitizer)) and negative)	EPO; JPO;	
		and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying	DERWENT	
		applied coated spin-coated spin-coat (spin		
		adj (coated coat coating))) and (irradiate		
		irradiating expose exposure exposing exposed		
		irradiated irradiation) and (develop development developing developed]) and		
		((visible adj light) "VIS"))) and (peel		
		peeling peelable peeled (peel\$4-apart)		
		(peel\$4 near apart))) and ((visible VIS)		
_	0	near light) ((((((resin resist photoresist binder) and	USPAT;	2003/07/07 17:02
		((photoacid acid) near generator) and	US-PGPUB;	2003/07/07 17.02
		(photosensitizer sensitizer)) and negative)	EPO; JPO;	
		and ((dry drying heat-treat\$5 (heat\$5) bak\$4	DERWENT	
		pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin		
		adj (coated coat coating))) and (irradiate		
		irradiating expose exposure exposing exposed		
		irradiated irradiation) and (develop		
		development developing developed]) and ((visible adj light) "VIS"))) and (peel		
		peeling peelable peeled (peel\$4-apart)		
1		(peel\$4 near apart))) and ((visible VIS)		
		near light)) and benzopyran		2002/07/07 17 00
-	0,	(((((resin resist photoresist binder) and ((photoacid acid) near generator) and	USPAT; US-PGPUB;	2003/07/07 17:02
		(photosensitizer sensitizer)) and negative)	EPO; JPO;	
		and ((dry drying heat-treat\$5 (heat\$5) bak\$4	DERWENT	
		pre-bake\$4) and (coat coating apply applying		
		applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate		
		irradiating expose exposure exposing exposed		
		irradiated irradiation) and (develop		
·		development developing developed]) and		
		((visible adj light) "VIS"))) and (peel peeling peelable peeled (peel\$4-apart)		
		(peel\$4 near apart))) and benzopyran		
-	2248		USPAT;	2003/07/07 17:02
			US-PGPUB; EPO; JPO;	
			DERWENT	
-	395	(((visible adj light) "VIS") and benzopyran)	USPAT;	2003/07/07 17:03
		and ((visible VIS) near light)	US-PGPUB;	
			EPO; JPO; DERWENT	
-	293	(resin resist photoresist binder) and	USPAT;	2003/07/07 17:03
		((((visible adj light) "VIS") and	US-PGPUB;	,,
		benzopyran) and ((visible VIS) near light))	EPO; JPO;	
	21	((nhotoacid acid) near cenerate?) and	DERWENT	2003/07/07 17:45
-	21	((photoacid acid) near generat\$3) and ((resin resist photoresist binder) and	USPAT; US-PGPUB;	2003/07/07 17:45
		((((visible adj light) "VIS") and	EPO; JPO;	
	_	benzopyran) and ((visible VIS) near light)))	DERWENT	
-	1	ls-148	USPAT; US-PGPUB;	2003/07/07 18:04
			EPO; JPO;	
			DERWENT	
-	2	JP-11258798-\$.DID.	USPAT;	2003/07/07 18:04
	,		US-PGPUB; EPO; JPO;	
			DERWENT	
1				I

-	2	benzopyran adj condensed adj ring	USPAT;	2003/07/08 11:34
-			US-PGPUB;	1
			EPO; JPO;	
			1	
			DERWENT	
-	7521	condensed adj ring	USPAT;	2003/07/08 11:53
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
				0000/07/00 10 40
-	72	proliferating adj agent	USPAT;	2003/07/08 13:48
			US-PGPUB;	
	1		EPO; JPO;	
1	1		DERWENT	
i _	2661	sodium adj lamp	USPAT;	2003/07/08 12:09
	2001	Southin adj tamp	· ·	2003/07/08 12:03
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	120	(sodium adj lamp) same (nm wavlength)	USPAT;	2003/07/08 12:10
			US-PGPUB;	
			EPO; JPO;	
			1 ' '	
			DERWENT	
-	72	proliferating adj agent	USPAT;	2003/07/08 14:31
			US-PGPUB;	
1			EPO; JPO;	
			DERWENT	
	1	in 00120502 & did	1	2002/07/08 13-50
-	2	jp-09138502-\$.did.	USPAT;	2003/07/08 13:50
· ·			US-PGPUB;	
	{		EPO; JPO;	
	1		DERWENT	
l _	2	("6140025").PN.	USPAT;	2003/07/08 14:06
	_	(0110023 / 11111	US-PGPUB;	2003,07,00 11100
			1	1
			EPO; JPO;	
			DERWENT	1
_	12	(proliferating adj agent) and (resin resist	USPAT;	2003/07/08 14:09
†		photoresist)	US-PGPUB;	' '
		photocostocy	EPO; JPO;	
], _,_ , _, _, _, _, _, _, _, _, _, _, _,	DERWENT	1
-	0	(proliferating adj agent) same ((fluidity	USPAT;	2003/07/08 14:35
		adj adjuster) (adhesion adj improver)	US-PGPUB;	
		(cissing adj inhibitor) (polymerization adj	EPO; JPO;	
}		inhibitor) pigment plasticizer)	DERWENT	
_	134		USPAT;	2003/07/08 14:58
1 -	134			2003/07/08 14:58
		adj adjuster) (adhesion adj improver)	US-PGPUB;	i
	1	(cissing adj inhibitor) (polymerization adj	EPO; JPO;	
		inhibitor) pigment plasticizer)	DERWENT	
-	83		USPAT;	2003/07/08 14:58
		((fluidity adj adjuster) (adhesion adj	US-PGPUB;	''''
		improver) (cissing adj inhibitor)	EPO; JPO;	
		(polymerization adj inhibitor) pigment	DERWENT	
		plasticizer)) and (resist photoresist resin)		1
-	79	((organic adj acid adj ester) same	USPAT;	2003/07/08 14:46
		((fluidity adj adjuster) (adhesion adj	EPO; JPO;	'
	1	improver) (cissing adj inhibitor)	DERWENT	
	1	(polymerization adj inhibitor) pigment		
		plasticizer)) and (resist photoresist resin)	l	/-
-	2648	(organic adj acid adj ester)	USPAT;	2003/07/08 14:58
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
	1070	((organia add agid add agreen)) and (resting		2002/07/08 14-50
_	1070	((organic adj acid adj ester)) and (resist	USPAT;	2003/07/08 14:59
		photoresist resin)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	834	((organic adj acid adj ester)) and (resist	USPAT	2003/07/08 15:13
		photoresist resin)		-105, 0., 00 15.15
	1	•	IICDAM	2003/07/00 15 00
-	0	430.270.1.ccls.	USPAT	2003/07/08 15:00
-	2718	l '	USPAT	2003/07/08 15:09
-	5	430/270.1.ccls. and (((organic adj acid adj	USPAT	2003/07/08 15:01
		ester)) and (resist photoresist resin))]	
1_	6	l	USPAT	2003/07/08 15:08
1			33171	2003, 07, 00 15:08
		ester))	L	

-	1	(430/270.1.ccls. and ((organic adj acid adj	USPAT	2003/07/08 15:08
		ester))) not (430/270.1.ccls. and		
		(((organic adj acid adj ester)) and (resist		
		photoresist resin)))		
-	112	430/\$.ccls. and ((organic adj acid adj	USPAT	2003/07/08 15:11
		ester))		
-	5270	430/\$.ccls. and (organic adj acid)	USPAT	2003/07/08 15:12
-	280	430/270.1.ccls. and (organic adj acid)	USPAT	2003/07/08 15:12
-	269	(430/270.1.ccls. and (organic adj acid)) and	USPAT	2003/07/08 15:23
		(resist photoresist resin)		
_	89	((430/270.1.ccls. and (organic adj acid))	USPAT	2003/07/08 15:30
		and (resist photoresist resin)) and (visible		
		near light)		
_	44	(((430/270.1.ccls. and (organic adj acid))	USPAT	2003/07/08 16:20
		and (resist photoresist resin)) and (visible		
		near light)) and negative		
-	97		USPAT	2003/07/08 16:21
l		generator) and (photosensitizer sensitizer)		
		and (visible near light)	<u>}</u>	·
_	155		USPAT:	2003/07/08 16:22
			US-PGPUB;	, ,
			EPO; JPO;	
			DERWENT	
_	2	(positive and ((photoacid acid) near	USPAT;	2003/07/08 16:33
		generator) and (photosensitizer sensitizer)	US-PGPUB;	1,11,11 = 1100
		and (visible near light)) and (IMAI-G	EPO; JPO;	
		IMAI-GENICHI IMAI-GENJI)	DERWENT	
_	2	,	USPAT:	2003/07/08 16:33
		(3301111 / 11111	US-PGPUB;	=====================================
			EPO; JPO;	
			DERWENT	
1	1	I and the second		